Typical Operating Parameters For HCD Silicon Nitride

**Tool:** TEL Alpha 8-SE

**Wafer:** 8”

**Gases:** Hexachlorodisilane, Ammonia

**System Base Pressure:** 15 Millitorr

**System Process Pressure:** 250 Millitorr

**Pumping System:** Edwards iQDP 80 / QMB 500

**Vacuum Lines:** ISO 100

**Exhaust Lines:** NW 50

**PM requirement before installation of MULTI-TRAP:** 112 Runs

**PM requirement after installation of MULTI-TRAP:** 480 Runs

**Comments:**

HCD Nitride produces 3 times the amount of ammonium chloride byproduct of the standard DCS Nitride process. Before the installation of the MULTI-TRAP the dry pumps failed on a weekly basis and the TEL trap clogged every 112 runs. The MULTI-TRAP was installed in front of the dry pump/blower package. Since the installation, the dry pump has been running for 2 months and the MULTI-TRAP is serviced every 480 runs. In this application the MULTI-TRAP paid for itself in less than 2 weeks.

MV MULTI-TRAP is the registered trade mark of MV Products Div., MASS-VAC, Inc.